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Assistant Commissioner for Patents
Washington, D.C. 20231

On

February 25, 2002

TOWNSEND and TOWNSEND and CREW LLP

By

[Signature]

#111D
3/18/02
MW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



In re application of:

David Cheung et al.

Application No.: 09/418,818

Filed: October 15, 1999

For: METHOD AND APPARATUS FOR
DEPOSITING ANTIREFLECTIVE
COATING

Examiner: Rudy Zervigon

Art Unit: 1763

AMENDMENT

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Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action mailed October 23, 2001, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claim 4 as follows. The remaining claims are unamended, but are reproduced below for the Examiner's convenience and reference.

1. A substrate processing system, comprising:

a vacuum chamber;

a substrate supporter, located within the vacuum chamber, for holding a substrate;

a gas manifold for introducing process gases into the chamber;

a gas distribution system, coupled to the gas manifold, for distributing the process gases to the gas manifold from gas sources;

5.1